

List of Publications

List of publications

(1) Papers

1. Yoshihiko Shoji
“**Identification of longitudinal coherent oscillation induced by path-length fluctuation**”
Phys. Rev. ST-AB, Vol.11, 010701 (2008).
2. Yoshihiko Shoji
“**Measurement of the time structure of a coherent synchrotron radiation burst in NewSUBARU**”
Infrared Physics and Technologies, Vol.51, Issue 5, pp.367-370 (2008).
3. Yoshihiko Shoji, Takao Asaka, Hideki Dewa, Hirohumi Hanaki, Yoshinori Hisaoka, Toshiaki Kobayashi, Takahiro Matsubara, Takayuki Mitsui, Akihiko Mizuno, Shinsuke Suzuki, Tsutomu Taniuchi, Hiromitsu Tomizawa, and Kenichi Yanagida
“**Bunch compression at the SPring-8 linac and successive generation of THz pulse train in the isochronous ring**”
Infrared Physics and Technologies, Vol.51, Issue 5, pp.394-396 (2008).
4. Takayuki Mitsui, and Yoshihiko Shoji
“**Beam-based Design of a Correction Coil for the Stray Field of a Pulse Septum Magnet**”
IEEE Transactions on Applied Superconductivity, Vol.18, No.2, pp.1521-1524 (2008).
5. Takeshi Nakamura, Keiko Kumagai, Yoshihiko Shoji, Ainosuke Ando, Satoshi Hashimoto, Noritaka Kumagai, Sakuo Matsui, Haruo Ohkuma, Takashi Ohshima, and Hideki Takebe
“**AC Sextupole Magnet for Cure of Transverse Instability in Synchrotron**”
IEEE Transactions on Applied Superconductivity, Vol.18, No.2, pp.326-329 (2008).
6. N. Nakanii, K. Kondo, T. Yabuuchi, K. Tsuji, and K. A. Tanaka, S. Suzuki, T. Asaka, K. Yanagida, and H. Hanaki, T. Kobayashi, K. Makino, and T. Yamane, S. Miyamoto, and K. Horikawa
“**Absolute calibration of imaging plate for GeV electrons**”
Rev. Sci. Instrum., Vol.79, pp. 066102- 1-3 (2008).
7. Akihisa Nagano, Takayasu Mochizuki, Shuji Miyamoto and Sho Amano
“**Laser wavelength dependence of extreme ultraviolet light and particle emissions from laser-produced lithium plasma**”
Appl. Phys. Lett., Vol.93, 091502 (2008).
8. Shuji Miyamoto
“**Laser Compton Scattering Gamma-ray Beam Line on NewSUBARU Synchrotron Facility**”
J. Particle Accelerator Soc. Jpn., Vol.5, No.2, August, pp.111-116 (2008). (in Japanese)
9. T. Hayakawa, T. Shizuma, S. Miyamoto, S. Amano, K. Horikawa, K. Ishihara, M. Mori, K. Kawase, M. Kando, N. Kikuzawa, S. Chiba, T. Mochizuki, T. Kajino, M. Fujiwara
“**Half-life of ^{164}Ho isomer populated in (γ, n) reactions with laser Compton scattering γ -rays at NewSUBARU**”
Phys. Rev. C Vol.77, 068801 (2008).
10. Yoshikazu Miyahara
“**Luminosity of angled collision of strongly focused beams with different Gaussian distributions**”
Nuclear Instruments and Methods in Physics Research A588, pp.323-329(2008).
11. Shuji Miyamoto, Ken Horikawa
“**NewSUBARU Gamma-ray Source and Application Research**”
Rev. of Laser Engineering, Vol.36, No.12, pp.798-805 (2008). (in Japanese)
12. Z. Insepov, M. Terasawa, K. Takayama
“**Surface erosion and modification by highly charged ions**”
Phys. Rev. A Vol.77, 062901 (2008).

13. Dazhi Li, Kazuo Imasaki, Shuji Miyamoto, Sho Amani, and Takayasu Mochizuki
“Nuclear Transmutation through Laser Compton Scattering Gamma-ray”
 “Nuclear Waste Research: Siting, Technology and Treatment”, Editor: Arnold P. Lattefer, Nova Science Publication, Inc., New York, ISBN **978-1-60456-184-5**, pp.189-205 (2008).
14. S.Amano, A.Nagano, T.Inoue, S.Miyamoto, T.Mochizuki
“EUV light source by laser-produced plasmas using cryogenic Xe and Li targets”
 Rev. Laser Eng., Vol.**36**, pp.715-720 (2008).
15. S.Amano, K.Horikawa, K.Ishihara, S.Miyamoto, T.Hayakawa, T.Shizuma, T.Mochizuki,
“Several-MeV g-ray generation at NewSUBARU by laser Compton backscattering”
 Nucl. Instrum. and Methods A, Vol.**602**, pp.337-341 (2009).
16. A.Nagano, S.Amano, S.Miyamoto, T.Mochizuki
“Extreme ultraviolet source using laser-produced Li plasmas”
 IEEJ Trans.EIS, Vol.**129**, No.2, p.249 (2009).
17. Yuichi Utsumi, Takefumi Kishimoto, Tadashi Hattori, and Megumi Minamitani,
“Proposal of Next-Generation Three-Dimensional X-Ray Lithography and Its Application to Fabrication of a High-Luminescence Optical Waveguide for a Liquid Crystal Backlight Unit”
 Electrical Engineering in Japan, Vol.**165**, No. 1, pp.52-59 (2008).
18. Yoshiaki Ukita, Mitsuyoshi Kishihara, Yuichi Haruyama, Kazuhiro Kanda, Shinji Matsui, Kozo Michiji, and Yuichi Utsumi,
“Fabrication of Polytetrafluoroethylene microparts by High-Energy X-ray Induced Etching”
 Jpn. J. Appl. Phys., Vol.**47**, pp.337-341 (2008).
19. Yoshiaki Ukita, Toshifumi Asano, Kuniyo Fujiwara, Katsuhiko Matsui, Masahiro Takeo, Seiji Negoro, Tomohiko Kanie, Makoto Katayama, and Yuichi Utsumi,
“Application of vertical microreactor stack with polystyrene microbeads to immunoassay”
 Sensors and Actuators A, Vol.**145-146**, pp.449-455 (2008).
20. Yuichi Utsumi, Tomohiro Ikeda, Megumi Minamitani, Kazuo Suwa,
“Integrated Structure of PMMA Microchannels for DNA Separation by Microchip Capillary Electrophoresis”
 Microsystem Technologies, Vol.**14**, pp.1461-1466 (2008).
21. Yuichi Utsumi, Toshifumi Asano, Yoshiaki Ukita, Katsuhiko Matsui, Masahiro Takeo, Seiji Negoro,
“High sensitive immunoassay for endocrine disrupting chemicals using antibody immobilized microcapillary bundle structure”
 Microsystem Technologies, Vol.**14**, pp.1399-1403 (2008).
22. Harutaka Mekaru, Takayuki Takano, Yoshiaki Ukita, Yuichi Utsumi, Masaharu Takahashi,
“A Si stencil mask for deep X-ray lithography fabricated by MEMS technology”
 Microsystem Technologies, Vol.**14**, pp.1335-1342 (2008).
23. Yoshiaki Ukita, Toshifumi Asano, Kuniyo Fujiwara, Katsuhiko Matsui, Masahiro Takeo, Seiji Negoro, Makoto Katayama, Tomohiko Kanie, and Yuichi Utsumi,
“Enzyme-Linked Immuno Sorvent Assay using vertical Microreactor Stack with Microbeads”
 Microsystem Technologies, Vol.**14**, pp.1573-1579 (2008).
24. Yoshiaki Ukita, Kazuhiro Kanda, Shinji Matsui, Mitsuyoshi Kishihara, and Yuichi Utsumi,
“Polytetrafluoroethylene Processing Characteristics using High-Energy X-ray”
 Microsystem Technologies, Vol.**14**, pp.1567-1572 (2008).
25. Kuniyo Fujiwara, Yoshiaki Ukita, Masahiro Takeo, Seiji Negoro, Tomohiko Kanie, Makoto, Katayama, and Yuichi Utsumi,
“High Efficiency Mixing by the Use of Cross-Linked Micro Capillary Fluid Filter”
 Microsystem Technologies, Vol.**14**, pp.1411-1416 (2008).

26. Mitsuyoshi Kishihara, Yoshiaki Ukita, Yuichi Utsumi, and Isao Ohta,
“Fabrication of a PTFE-Filled Waveguide for Millimeter-Wave Components Using SR Direct Etching Process”
 Microsystem, Technologies, Vol.14, pp.1417-1422 (2008).
27. Daisuke Fukuoka, and Yuichi Utsumi, **“Fabrication of the Cyclical Fluid Channel using The Surface Acoustic Wave Actuator and Continuous Fluid Pumping in the Cyclical Fluid”**
 Microsystem Technologies, Vol.14, pp.1395-1398 (2008).
28. S. Suzuki, Y. Fukushima, R. Ohnishi, T. Watanabe, and H. Kinoshita
“Pattern Replication in EUV Interference Lithography”
 J. Photopolym. Sci. Technol. Vol.21, pp.435-438 (2008).
29. Y. Fukushima, T. Watanabe, R. Ohnishi, H. Kinoshita, S. Suzuki, S. Yusa, Y. Endo, M. Hayakawa, and T. Yamanaka
“PAG Study of PAG Bonded Resist for EUV and EB Lithography”
 J. Photopolym. Sci. Technol. Vol.21, pp.465-468 (2008).
30. Yasuyuki Fukushima, Takeo Watanabe, Ryuji Ohnishi, Hideaki Shiotani, Shota Suzuki, Masamichi Hayakawa, Yusuke Endo, Tomotaka Yamanaka, Shinichi Yusa and Hiroo Kinoshita
“Optimization of Photo Acid Generator in the PAG-Bonded Resist”
 Jpn. J. Appl. Phys., Vol.47, pp.6293-6296 (2008).
31. Hideaki Shiotani, Shota Suzuki, Dong Gun Lee, Patrick Naulleau, Yasuyuki Fukushima, Ryuji Ohnishi, Takeo Watanabe and Hiroo Kinoshita
“Dual Grating Interferometric Lithography for 22-nm Node”
 Jpn. J. Appl. Phys. Vol.47, pp.4881-4885 (2008).
32. Masafumi Osugi, Kazuumi Tanaka, Noriyuki Sakaya, Kazuhiro Hamamoto, Takeo Watanabe and Hiroo Kinoshita,
“Resolution Enhancement of EUV Microscope Using an EUV Beam Splitter”
 Jpn. J. Appl. Phys. Vol.47, pp.4872-4877 (2008).
33. M. Hosoya, N. Sakaya, O. Nozawa, K. Hamamoto, O. Nagarekawa, T. Watanabe and H. Kinoshita
“Evaluation Method of Optical Index of Ta and Ta-based Absorber for EUV Mask Using Extreme Ultraviolet Reflectometer”
 Jpn. J. Appl. Phys. Vol.47, pp.4898-4905 (2008).
34. Takanori Owada, Takeo Watanabe, Hiroo Kinoshita, Hiroaki Oizumi, and Iwao Nishiyama,
“Development of novel positive-tone resists for EUVL”
 Proc. SPIE Vol.6923, 692346-1-7 (2008).
35. Sungmin Huh, Hoon Kim; Gisung Yoon, Jaehyuck Choi, Han-Shin Lee, Dong Gun Lee, Byungsup Ahn, Hwan-Seok Seo, Dongwan Kim, Seoung Sue Kim, Han Ku Cho, Takeo Watanabe, Hiroo Kinoshita,
“Lifetime of EUVL masks as a function of degree of carbon contamination and capping materials”
 Proc. SPIE Vol.6921, pp.692115-1-9 (2008).
36. Takashi Sasaki, Osamu Yokokoji, Takeo Watanabe, and Hiroo Kinoshita
“Development of partially fluorinated EUV-resist polymers for LER and sensitivity improvement”
 Proc. SPIE Vol.6923, pp.692347-1-7 (2008).
37. T. Watanabe and H. Kinoshita
“Current Status and Prospect of Extreme Ultraviolet Lithography”
 J. Photopolym. Sci. Technol., Vol.21, pp.777-784 (2008).
38. Noriko Yamada, Kazuhiro Kanda, Akihiko Saikubo, Masahito Niibe, Yuichi Haruyama, and Shinji Matsui,
“Fabrication of fluorocarbon terminated DLC thin film using soft X-ray”
 Diamond and Related Materials, Vol. 17, pp.655-658 (2008).

39. Akihiko Saikubo, Jun-ya Igaki, Reo Kometani, Kazuhiro Kanda, and Shinji Matsui,
“XAFS measurement of gallium in DLC thin film fabricated by FIB-CVD method”
 Diamond and Related Materials, Vol.17, pp.659-663 (2008).
40. Haruhiko Ito, Kazuhiro Kanda, and Hidetoshi Saitoh,
“Deposition of mechanically hard amorphous carbon nitride films with high [N]/([N]+[C]) ratio”
 Diamond and Related Materials, Vol.17, pp.688-691 (2008).
41. Haruhiko Ito, Taro Nozaki, Akihiko Saikubo, Noriko Yamada, Kazuhiro Kanda, Masahito Niibe, and
 Hidetoshi Saitoh,
“Hydrogen-storage characteristics of hydrogenated amorphous carbon nitrides”
 Thin Solid Films, Vol.516, pp.6575-6579 (2008).
42. Kazuhiro Kanda, Jun-ya Igaki, Reo Kometani, Shinji Matsui and Haruhiko Ito,
**“Characterization of high nitrogen content-amorphous carbon nitride films using NEXAFS
 spectroscopy”**
 Diamond & Related Materials, Vol.17, pp.1755-1758 (2008).
43. Reo Kometani, Sunao Ishihara, Kazuhiro Kanda, Yuichi Haruyama, Takashi Kaito, and Shinji Matsui,
**“Eduction Position Control of Incorporated Gallium in Diamond-Like Carbon Deposited by
 Focused-Ion-Beam Chemical Vapor Deposition”**
 Jpn. J. Appl. Phys., Vol.47, pp.5032-5035 (2008).
44. Makoto Okada, Ken-ichiro Nakamatsu, Kazuhiro Kanda, Yuichi Haruyama, Reo Kometani, Takashi
 Kaito, and Shinji Matsui,
“Examination of Focused-Ion-Beam Repair Resolution for UV-Nanoimprint Templates”
 Jpn. J. Appl. Phys., Vol. 47, pp.5160-5163 (2008).
45. Kazuhiro Kanda, Jun-ya Igaki, Akihiko Saikubo, Reo Kometani, Tsuneo Suzuki, Koichi Niihara,
 Hidetoshi Saitoh, and Shinji Matsui,
**“Effects of Annealing on Material Characteristics of Diamond-Like Carbon Film Formed by
 Focused-Ion-Beam Chemical Vapor Deposition”**
 Jpn. J. Appl. Phys., Vol.47, pp.7464-7466 (2008).
46. Makoto Okada, Masayuki Iwasa, Ken-ichiro Nakamatsu, Noriko Yamada, Kazuhiro Kanda, Yuichi
 Haruyama, and Shinji Matsui, **“Temperature Dependence of Release Effect for Antisticking Layer
 in Nanoimprint Characterized by Scanning Probe Microscopy”**
 Jpn. J. Appl. Phys., Vol. 47, pp.7467-7469 (2008).
47. Takahiro Nagata, Yoshiki Samuka, Masamitsu Haemori, Kiyomi Nakajima, Reo Kometani, Kazuhiro
 Kanda, Shinji Matsui, and Toyohiro Chikyow,
**“Effect of Annealing on Implanted Ga of Diamond-Like Carbon Thin Films Fabricated by
 Focused-Ion-Beam Chemical Vapor Deposition”**
 Jpn. J. Appl. Phys., Vol.47, pp.9010-9012 (2008).
48. Akihiko Saikubo, Noriko Yamada, Kazuhiro Kanda, Shinji Matsui, Tsuneo Suzuki, Koichi Niihara,
 and Hidetoshi Saitoh ,
**“Comprehensive classification of DLC films formed by various methods using NEXAFS
 measurement”**
 Diamond & Related Material, Vol.17, pp.1743-1745 (2008).
49. M. Okada, M. Iwasa, K. Nakamatsu, N. Yamada, K. Kanda, Y. Haruyama, and S. Matsui
**“Evaluation of fluorinated diamond like carbon as antisticking layer by scanning probe
 microscopy”**
 Journal of Photopolymer Science and Technology, Vol.21, pp.597-599 (2008).
50. K. Nakamatsu, M. Okada, C. Minari, Y. Takeuchi, N. Taneichi, S. Ohtaka, and S. Matsui,
**“Effect of UV Irradiation on Microlens Arrays Fabricated by Room Temperature
 Nanoimprinting Using Organic Spin-on-Glass”**
 Appl. Phys. Express., Vol.1, 067002 (2008).

51. K. Nakamatsu, M. Okada, and S. Matsui, “**Fabrication of High-Aspect Si Structures by Deep Reactive Ion Etching Using Hydrogen Silsesquioxane Masks Replicated by Room Temperature Nanoimprinting**”
Jpn. J. Appl. Phys., Vol. **47**, 8619 (2008).
52. Katsuhiro Nishihara, Masamitsu Matsumoto, Masanari Kimoto, Takeo Kudo, Hitoshi Uchida, Yuichi Haruyama, Kazuhiro Kanda, Shinji Matsui
“**Structure Analysis of Thin Corrosion Product Films on Hot-dip Zn-Al Coatings Using Soft X-ray Synchrotron Radiation**”(in Japanese)
Zairyo-to-Kankyo, Vol.**57**(2), pp.76-80 (2008).
53. Kazuhiro Kanda
“**Surface Modification of DLC Thin Films Using Synchrotron Radiation Process under per-fluorohexane atmosphere**”(in Japanese)
NEW DIAMOND, Vol.**89**, pp.30-31 (2008).
54. Y. Haruyama, T. Kitagawa, K. Kanda, S. Matsui, T. Gejo, N. Toyoda, I. Yamada
“**X-Ray Photoelectron Spectroscopy Study of Diamond-Like Carbon Thin Films Formed by Ar Gas Cluster Ion Beam-Assisted Fullerene Deposition**”
Jpn. J. Appl. Phys., Vol.**47**, pp.3380-3383 (2008).
55. Katsuhiro Nishihara, Masamitsu Matsumoto, Masanari Kimoto, Takeo Kudo, Hitoshi Uchida, Yuichi Haruyama, Kazuhiro Kanda, and Shinji Matsui
“**Application of Synchrotron Radiation Photoemission Spectroscopy to Structure Analysis of Thin Corrosion Product Films on Hot-Dip Zn-Al Coatings**”
ECS Trans. 11, Issue 22, pp.39-44 (2008).
56. Yuichi Haruyama, Yoshihiro Aiura, Hiroshi Bando, Shinji Matsui
“**Photoemission study of the Au-SrTiO₃(100) surface**”
IEEJ Transactions on Electronics, Information and Systems, Vol.**129**, pp.225-228 (2009).
57. Taichi Okuda, Toyoaki Eguchi, Kotone Akiyama, Ayumi Harasawa, Toyohiko Kinoshita, Yukio Hasegawa, Masanori Kawamori, Yuichi Haruyama, and Shinji Matsui
“**Nano-Scale Chemical Imaging by Synchrotron Radiation Assisted Scanning Tunneling Microscopy**”
Phys. Rev. Lett. Vol.**102**, pp.105503-4 (2009).
58. M. Niibe, K. Miyamoto, T. Mitamura, K. Mochiji:
“**Identification of B-K XANES Peaks of BN Thin Film Prepared by Sputtering Deposition**”
Bulletin Soc. Discrete Variational X α , Vol.**21**, pp.179-182 (2008).
59. M. Niibe, K. Koida and Y. Kakutani:
”**Protection and reduction of surface oxidation of Mo/Si multilayers for extreme ultraviolet lithography projection optics by control of hydrocarbon gas atmosphere**”
J. Vac. Sci Technol., B Vol. **26**, pp.2230-2235 (2008).
60. Masahito Niibe and Hisataka Takenaka,
“**Application and Development of Soft X-ray Multilayers for Optical Elements**” (in Japanese)
O plus, E Vol.**30**, pp.860-864 (2008).
61. Daiji Noda, Shuhei Yamashita, Yoshifumi Matsumoto, Masaru Setomoto, and Tadashi Hattori,
“**Fabrication of High Aspect Ratio Microcoil Using by Dipping Method**”
Journal of Advanced Mechanical Design, Systems, and Manufacturing, Vol.**2**, pp.174-179 (2008).
62. Kyo Tanabiki, Youichi Funabiki, Daiji Noda, and Tadashi Hattori,
“**Fabrication of the 3 Dimension Resist Microstructure Using X-ray Diffraction**”
Journal of Advanced Mechanical Design, Systems, and Manufacturing, Vol.**2**, pp.191-196 (2008).
63. Kazufumi Nishimoto, Naoya Ishizawa, Hiroyasu Ueda, Daiji Noda, and Tadashi Hattori,
“**Surface Modification and Direct Bonding of Different Materials Irradiated H₂O Ion**”
Journal of Advanced Mechanical Design, Systems, and Manufacturing, Vol.**2**, pp.197-202 (2008).

64. Masaru Setomoto, Yoshifumi Matsumoto, Shuhei Yamashita, Daiji Noda, and Tadashi Hattori,
“Fabrication of Spiral Micro Coil Lines for Electromagnetic Actuators”
 Journal of Advanced Mechanical Design, Systems, and Manufacturing, Vol.2, No.2, pp.238-245
 (2008).
65. Hiroshi Tsujii, Kazuma Shimada, Makoto Tanaka, Daiji Noda, and Tadashi Hattori,
“Fabrication of the X-ray Mask Using the Silicon Dry Etching”
 Journal of Advanced Mechanical Design, Systems, and Manufacturing, Vol.2, No.2, pp.246-251
 (2008).
66. Daiji Noda, Yoshifumi Matsumoto, Masaru Setomoto, and Tadashi Hattori,
“Fabrication of Microcoils Using X-ray Lithography and Metallization”
 IEEE Transactions on Sensors and Micromachines, Vol.128, No. 5, pp. 181-185 (2008).
67. Daiji Noda, Makoto Tanaka, Kazuma Shimada, Wataru Yashiro, Atsushi Momose, and Tadashi
 Hattori,
“Fabrication of Large Area Diffraction Grating Using LIGA Process”
 Microsystem Technologies, Vol.14, No.9-11, pp.1311-1315 (2008).
68. Yoshifumi Matsumoto, Masaru Setomoto, Daiji Noda, and Tadashi Hattori,
**“Cylindrical Coils Created with 3D X-ray Lithography and Metallization for Electromagnetic
 Actuators”**
 Microsystem Technologies, Vol.14, No.9-11, pp.1373-1379 (2008).
69. Naoya Ishizawa, Kazuyoshi Idei, Taro Kimura, Daiji Noda, and Tadashi Hattori,
“Resin Micromachining by Roller Hot Embossing”
 Microsystem Technologies, Vol. 14, No. 9-11, pp.1381-1388 (2008).
70. Yoshitaka Sawa, Takanori Tanaka, Takeshi Kitadani, Hiroshi Ueno, Koichi Itoigawa, Kenji Yamashita,
 Daiji Noda, and Tadashi Hattori,
“Development of Lighting Panel Comprising Light Tube Fabricated by LIGA Process”
 Microsystem Technologies, Vol.14, No.9-11, pp.1559-1565 (2008).
71. Tadashi Hattori,
“Recent Advances and Prospects of Precise 3D Microfabrication with a High Aspect Ratio”
 Chemical Industry, Vol.59, No.8, pp.620-626 (2008).
72. Yoshihio Takeda, Wataru Yashiro, Tadashi Hattori, Akihisa Takeuchi, Yoshio Suzuki, and Atsushi
 Momose,
“Differential Phase X-ray Imaging Microscopy with X-ray Talbot Interferometer”
 Applied Physics Express, Vol.1, No.11, pp.117002-1-3 (2008).
73. Daiji Noda, Hiroshi Tsujii, Kazuma Shimada, Wataru Yashiro, Atsushi Momose, and Tadashi Hattori,
“Fabrication of High Aspect Ratio X-ray Grating Using X-ray Lithography”
 Journal of Solid Mechanics and Materials Engineering, Vol.3, No.2, pp.416-423 (2009).
74. Harutaka Mekaru, Shinji Kusumi, Noriaki Sato, Masami Shimizu, Michiru Yamashita, Osamu
 Shimada, and Tadashi Hattori,
“Development of 3D-LIGA Process to Fabricate Spiral Microcoil”
 Electrical Engineering in Japan, Vol.166, No.1, pp.43-51 (2009).
75. Tadashi Hattori,
“Recent Advances and Prospects of High Aspect Ratio Precise 3D Microfabrication”
 Science and Machine, Vol.61, No.1, pp.10-16 (2009).
76. Daiji Noda, Yoshifumi Matsumoto, Masaru Setomoto, and Tadashi Hattori,
“Fabrication of Electromagnetic Microactuators with High Aspect Ratio Coil Lines”
 Journal of the Japan Society of Applied Electromagnetics and Mechanics, Vol.17, No.1, pp.162-167
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(2) International Meetings

1. N.Maysuo, Y.Takanashi, A.Heya, S.Isoda, K.Masuda, S.Amano, S.Miyamoto, T.Mochizuki,
”**Laser plasma soft x-ray irradiation onto a-Si film realizing low-temperature crystal growth**”
Int’l Thin Film Transistor Conference, S10-6, Paris (2009).
2. Yuichi Utsumi
”**Development of 3D Micro Prototyping using Synchrotron Radiation and Its Application to Bio Micro Systems**” (Keynote Speech)
The 7th Int’l Conf. on Machine Automation, JAPAN ,September 24-26 (2008).
3. Yuichi Utsumi, Tsunemasa Saiki, and Katsuhide Okada
”**Proposal of a Novel Continuous Flow Pumping Operated by SurfaceAcoustic Wave**”
12th Int’l Conf. on Miniaturized Systems for Chemistry and Life Sciences, San Diego, California, USA, October 12-16 (2008).
4. Tsunemasa Saiki, Katsuhide Okada, and Yuichi Utsumi
”**Proposal of a Micro Liquid Roter Operated by Surface Acoustic Wave**”
Twelfth Int’l Conference on Miniaturized Systems for Chemistry and Life Sciences, San Diego, California, USA, October 12-16 (2008).
5. Shigeaki Yamamoto, Takefumi Kishimoto, and Yuichi Utsumi,
”**Enhancement of the Adhesive Force of Metal films on PTFE Surface Achieved by Fast-Atom-Beam Surface Modification**”
Int’l Conference on Electronics Packaging 2008, pp36-39, JAPAN, June 10-12 (2008).
6. Daisuke Fukuoka, and Yuichi Utsumi,
”**Micro Fluid Device of PMMA for DNA Sequence by Using LIGA process and Fusion Bonding**”
Int’l Conference on Electronics Packaging, pp387-390, JAPAN, June 10-12 (2008).
7. Saki Kondo, Yoshiaki Ukita, Kuniyo Fujihara, and Yuichi Utsumi,
”**Cross-linked Capillary Micromixer for High-sensitive Immunoassay**”
Int’l Microprocess and Nanotechnology Conference, pp90-91, October 27-30 (2008).
8. Yoshiaki Ukita, Saki Kondo, and Yuichi Utsumi, ”**Vertical microreactor stack with cross-linked capillary structure for high-sensitive ELISA**”
34th Int’l Conference on Micro and Nano Engineering, 7C-2, Greece, September 15- 18 (2008).
9. Yoshiaki Ukita, Shigeaki Yamamoto, Mitsuyoshi Kishihara, Kozo Mochiji, and Yuichi Utsumi,
”**Smoothing of poly-(tetrafluoroethylene) by high-energy x-ray induced photo-chemical reactions**”
34th Int’l Conference on Micro and Nano Engineering, OL-P07, Greece, September 15- 18 (2008).
10. Yoshiaki Ukita, Shigeaki Yamamoto, and Yuichi Utsumi,
”**The Polytetrafluoroethylene Processing Characteristics of High-Energy (2 keV - 12 keV) X-Ray and its Application to Microfluidics**”
Int’l Conference on Electronics Packaging, 12B1-2, JAPAN, June 10- 12 (2008).
11. Yoshiaki Ukita, Tomoya Omukai, Saki Kondo, and Yuichi Utsumi,
”**The Advantages of Vertical Microreactor with Multifunctional Fluid Filter for Immunoassay**”
Int’l Coference on Electronics Packaging, 12B1-3, JAPAN, June 10- 12 (2008).
12. D. Atwood, H. Kinoshita, and P. Dunne
”**EUVL R&D Status Panel Discussion -The Role of Universities and National Laboratories in EUV Lithography-**”
Int’l Workshop on EUV Lithography, Maui, Hawaii, USA, June 10-12 (2008).

13. H. Kinoshita, T. Yoshizumi, M. Osugi, J. Kishimoto, T. Sugiyama, N. Sakaya, K. Hamamoto, and T. Watanabe
“EUV Mask Inspection system” (Invited Talk)
 Int’l Workshop on EUV Lithography, Maui, Hawaii, USA, June 10-12 (2008).
14. David Pui, H. Kinoshita, and K. Goldberg
“Mask Panel Symposium: Will Defects be the Last Issue Standing in the Way of EUV?”
 Int’l Workshop on EUV Lithography, Maui, Hawaii, USA, June 10-12 (2008).
15. J. Kishimoto, T. Watanabe, H. Kinoshita, Dong gun Lee, Seong-Sue Kim, and Han-Ku Cho
“Development of Coherent EUV Scattering Microscopy”
 Int’l Workshop on EUV Lithography, Maui, Hawaii, USA, June 10-12 (2008).
16. S. Suzuki, Y. Fukushima, R. Ohnishi, T. Watanabe, and H. Kinoshita,
“Pattern Replication in EUV Interference Lithography”
 The 25th Int’l Conference of Photopolymer Science and Technology, Chiba, Japan, June 24-27 (2008).
17. Y. Fukushima, T. Watanabe, R. Ohnishi, H. Kinoshita, S. Suzuki, S. Yusa, Y. Endo, M. Hayakawa, and T. Yamanaka,
“PAG Study of PAG Bonded Resist for EUV and EB Lithography”
 The 25th Int’l Conference of Photopolymer Science and Technology, Chiba, Japan, June 24-27 (2008).
18. Takeo Watanabe
“EUV Lithography”, Panel Symposium”
 The 25th Int’l Conference of Photopolymer Science and Technology, Chiba, Japan, June 24-27 (2008).
19. T. Watanabe, T. Geun Kim, S. Suzuki, M. Osugi, Y. Fukushima, H. Kinoshita, and T. Mochizuki
“EUV Interference Lithography Employing 11-m Long Undulator as a Light Source”
 Int’l Workshop on EUV Lithography, Maui, Hawaii, USA, June 10-12 (2008).
20. H. Kinoshita, T. Yoshizumi, M. Osugi, J. Kishimoto, T. Sugiyama, T. Uno, and T. Watanabe
“Study on critical dimension of printable phase defects using an EUV microscope”
 34th Int’l Conference on Micro and Nano Engineering, Athens, Greece, September 15-19 (2008).
21. H. Kinoshita, Y. Kamaji, K. Takase, T. Suguyama, T. Uno, and T. Watanabe
“Study on Critical Dimension of Printable Phase Defects using an EUV Microscope”
 7th EUVL Int’l Symposium, Lake Tahoe, California, USA, September 28-October 1 (2008).
22. D. Shiono, T. Watanabe, and H. Kinoshita
“Investigation of CA Resists Decomposition by EUV Exposure”
 7th EUVL Int’l Symposium, Lake Tahoe, California, USA, September 28-October 1 (2008).
23. T. Sasaki, O. Okokoji, T. Watanabe, and H. Kinoshita
“Development of Partially Fluorinated EUV-Resist Polymers for LER and Sensitivity Improvement”
 7th EUVL Int’l Symposium, Lake Tahoe, California, USA, September 28-October 1 (2008).
24. D. Shiono, T. Watanabe, and H. Kinoshita
“Decomposition Analysis of Chemically Amplified Resists to Further CD Control”
 21th Microprocesses and Nanotechnology Conference, Fukuoka, Japan, October 27-30 (2008).
25. Y. Kamaji, K. Takase, T. Uno, T. Watanabe, and H. Kinoshita
“Study on Critical Dimension of Printable Phase Defects using an EUV Microscope”
 21st Microprocesses and Nanotechnology Conference, Fukuoka, Japan, October 27-30 (2008).
26. R. Ohnishi, Y. Fukushima, M. Osugi, T. Watanabe, and H. Kinoshita
“Transmission Measurement using EUV Light for the Development of EUV Resist”
 21st Microprocesses and Nanotechnology Conference, Fukuoka, Japan, October 27-30 (2008).

27. Y. Fukushima, R. Ohnishi, T. Watanabe and, H. Kinoshita
“Effectiveness of the Fullerene Derivative Additive for EUV Resists”
 21st Microprocesses and Nanotechnology Conference, Fukuoka, Japan, October 27-30 (2008).
28. T. Nakahara, T. Watanabe, H. Kinoshita, T. Mochizuki, T. Takahara, Y. Uozumi and K. Nakagawa
“Amine Additives Effect in PAG-bonded Resist for EUV and EB Lithography”
 21st Microprocesses and Nanotechnology Conference, Hakata, Japan, October 27-30 (2008).
29. I. Aratani, S. Matsunaga, T. Kajiyashiki, T. Watanabe, and H. Kinoshita
“Evaluation of Novel Resist Materials for EUV Lithography”
 SPIE's 34 rd Annual Int'l Symposium on Advanced Lithography, San Jose, CA, USA, February 22 - 27 (2009).
30. D. Shiono, T. Watanabe, and H. Kinoshita
“Decomposition analysis of molecular resists to further CD control”
 SPIE's 34 rd Annual Int'l Symposium on Advanced Lithography, San Jose, CA, USA, February 22 - 27 (2009).
31. K. Kanda, J. Igaki, N. Yamada, R. Kometani, and S. Matsui,
“Graphitization of thin films formed by focused-ion-beam chemical-vapor-deposition”
 2nd Int'l Conference on New Diamond and Nano Carbons, Taipei, The Republic of China. (2008).
32. M. Okada, M. Iwasa, K. Nakamatsu, K. Kanda, Y. Haruyama, and S. Matsui,
“Evaluation of Release Effect of Antisticking Layer for Nanoimprint Resin by Scanning Probe Microscopy”
 1st Asian Symposium on Nanoimprint Lithography, Seoul, Korea (2008).
33. M. Okada, M. Iwasa, N. Yamada, K. Nakamatsu, K. Kanda, Y. Haruyama, and S. Matsui, **“Evaluation of Fluorinated Diamond Like Carbon as Antisticking Layer by Scanning Probe Microscopy”**
 The 26th Int'l Conference of Photopolymer Science and Technology Materials & Processes for Advanced Microlithography and Nanotechnology, Chiba, Japan, June 30 - July 3 (2009).
34. Y. Kang, M. Okada, K. Nakamatsu, K. Kanda, Y. Haruyama and S. Matsui,
”Room-Temperature Nanoimprint using Sol-Gel ITO film”
 The 26th Int'l Conference of Photopolymer Science and Technology Materials & Processes for Advanced Microlithography and Nanotechnology, Chiba, Japan, June 30 - July 3 (2009).
35. Y. Kang, M. Okada, K. Nakamatsu, K. Kanda, Y. Haruyama and S. Matsui,
”Room-Temperature Nanoimprint using Liquid-Phase Hydrogen Silsesquioxane with PDMS mold”
 The 26th Int'l. Conference of Photopolymer Science and Technology Materials & Processes for Advanced Microlithography and Nanotechnology, Chiba, Japan, June 30 - July 3 (2009).
36. M. Okada, M. Iwasa, K. Nakamatsu, K. Kanda, Y. Haruyama, and S. Matsui,
”Evaluation of Heat Durability for Antisticking Layer in Nanoimprint by Scanning Probe Microscopy”
 34th Micro and Nano Engineering, Athens, Greece (2008).
37. M. Okada, M. Iwasa, K. Nakamatsu, K. Kanda, Y. Haruyama, and S. Matsui,
”Nanoimprinting using Release Agent Coated Polymethylmethacrylate”
 34th Micro and Nano Engineering, Athens, Greece (2008).
38. M. Okada, T. Kishiro, K. Yanagihara, M. Ataka, N. Anazawa, and S. Matsui,
”Large Area Mold Fabrication by Electron-Beam Stepper”
 The 7th Int'l Conference on Nanoimprint and Nanoprint Technology, Kyoto, Japan (2008).
39. M. Okada, K. Nakamatsu, Y. Kang, K. Kanda, Y. Haruyama, and S. Matsui,
”Antisticking Layer Formed by CHF₃ Plasma irradiation for Nanoimprint Molds”
 The 7th Int'l Conference on Nanoimprint and Nanoprint Technology, Kyoto, Japan (2008).

40. M. Okada, M. Iwasa, K. Nakamatsu, Y. Kang, K. Kanda, Y. Haruyama, and S. Matsui,
"Room Temperature Nanoimprinting on a Release Agent Coated Hydrogen Silsesquioxane"
 The 7th Int'l Conference on Nanoimprint and Nanoprint Technology, Kyoto, Japan (2008).
41. M. Okada, M. Iwasa, K. Nakamatsu, Y. Kang, K. Kanda, Y. Haruyama, and S. Matsui,
"Nanoscale Release Effect Measurement of Antisticking Layer for Nanoimprint Resin by Scanning Probe Microscope"
 The 7th Int'l Conference on Nanoimprint and Nanoprint Technology, Kyoto, Japan (2008).
42. Y. Kang, M. Okada, K. Nakamatsu, K. Kanda, Y. Haruyama and S. Matsui,
"Nanofabrication of ITO film by Room-Temperature Nanoimprint"
 The 7th Int'l Conference on Nanoimprint and Nanoprint Technology, 14B2-5-54, Kyoto, Japan, October 13-15 (2008).
43. M. Okada, M. Iwasa, K. Nakamatsu, K. Kanda, Y. Haruyama, and S. Matsui,
"Nanoscale Release Effect of Antisticking Layer for Nanoimprint Resin Characterized by Scanning Probe Microscopy"
 American Vacuum Society 55th Int'l. Symposium, Boston, USA (2008).
44. M. Okada, T. Kishiro, K. Yanagihara, M. Ataka, N. Anazawa, and S. Matsui,
"Nanoimprint using Large Area Mold Fabricated by Electron-Beam Stepper"
 21st Int'l Microprocesses and Nanotechnology Conference, Fukuoka, Japan, October 27-30 (2008).
45. M. Okada, K. Nakamatsu, Y. Kang, K. Kanda, Y. Haruyama, and S. Matsui,
"Characteristics of Antisticking Layer Formed by CHF₃ Plasma irradiation for Nanoimprint Molds"
 21st Int'l. Microprocesses and Nanotechnology Conference, Fukuoka, Japan, October 27-30 (2008).
46. M. Okada, M. Iwasa, K. Nakamatsu, Y. Kang, K. Kanda, Y. Haruyama, and S. Matsui,
"Room Temperature Nanoimprint using Release Agent Coated Hydrogen Silsesquioxane Resin"
 21st Int'l Microprocesses and Nanotechnology Conference, Fukuoka, Japan, October 27-30 (2008).
47. M. Okada, M. Iwasa, K. Nakamatsu, Y. Kang, K. Kanda, Y. Haruyama, and S. Matsui, **"Examination of Nanoscale Release Effect between Antisticking Layer and Nanoimprint Resin by Scanning Probe Microscope"**
 21st Int'l Microprocesses and Nanotechnology Conference, Fukuoka, Japan, October 27-30 (2008).
48. Y. Kang, M. Okada, K. Nakamatsu, K. Kanda, Y. Haruyama and S. Matsui,
"Oxygen Plasma Irradiation Effect onto ITO patterned by Room-Temperature Nanoimprint"
 21st Int'l Microprocesses and Nanotechnology Conference, Fukuoka, Japan, October 27-30 (2008).
49. K. Kanda, Makoto Okada, and Shinji Matsui,
"Variation on Local Structure of DLC Thin Films Formed with FIB-CVD Method by Annealing"
 The IUMRS Int'l Conference in Asia, Nagoya, Japan, December 9-13 (2008).
50. M. Okada, K. Nakamatsu, Y. Kang, K. Kanda, Y. Haruyama, and S. Matsui,
"Nanoimprinting using CHF₃ Reactive Ion Etching Plasma Irradiated Mold"
 The IUMRS Int'l Conference in Asia, Nagoya, Japan, December 9-13 (2008).
51. Y. Kang, M. Okada, K. Nakamatsu, K. Kanda, Y. Haruyama and S. Matsui,
"Nanoimprint Mold Fabrication using Fluorinated Diamond-like Carbon"
 The IUMRS Int'l Conference in Asia, MP-21, Nagoya, Japan, December 9-13 (2008).
52. Y. Kang, M. Okada, K. Nakamatsu, K. Kanda, Y. Haruyama and S. Matsui,
"Effect of UV Irradiation on Sol-Gel ITO Nanopatterns Replicated by Room-Temperature Nanoimprint", 6C-3
 The 53rd Int'l Conference on Electron, Ion, and Photon Beam Technology and Nanofabrication, Florida, May 26-29 (2009).

53. Y. Haruyama, T. Kitagawa, K. Kanda, S. Matsui, N. Toyoda, I. Yamada
“Photoemission Study of Diamond-Like Carbon Thin Films Formed by Ar Gas Cluster Ion Beam-Assisted Fullerene Deposition”, Poster I-1
 21st Int’l Conference on X-ray and Inner-Shell Processes, Paris, France, June 22-27 (2008).
54. Y. Haruyama, T. Kitagawa, S. Matsui, N. Toyoda, I. Yamada
“Photoemission Study of Valence Band Region in Diamond-Like Carbon Thin Films”, 29P46
 4th Vacuum and Surface Sciences Conference of Asia and Australia, Matsue Japan, October 28-31 (2008),
55. T. Nakayama, H. Takase, S. Terashima, T. Sudo, Y. Watanabe, Y. Fukuda, K. Murakami, S. Kawata, T. Aoki, S. Matsunari, Y. Kakutani, M. Niibe, K. Koida:
”Analysis of deposition on multilayer mirrors using two different beam lines”
 SPIE 34th Int’l Symposium Microlithography, San Jose, USA, February 22-27 (2009).
56. S. Matsunari, Y. Kakutani, T. Aoki, K. Murakami, S. Kawata, T. Nakayama, S. Terashima, H. Takase, Y. Watanabe, Y. Gomei, Y. Fukuda, M. Niibe:
”Durability of capped multilayer mirror for high-volume manufacturing extreme-ultraviolet lithograph tool”
 SPIE 34th Int’l Symposium Microlithography, San Jose, USA, February 22-27 (2009).
57. Keigo Koida and Masahito Niibe:
“Study on contamination of projection optics surface for extreme ultraviolet lithography”
 4th Vacuum and Surface Sciences Conference of Asia and Australia, Matsue Japan, October 28-31 (2008).
58. M. Tagawa, K. Yokota, A. Kitamura, K. Matsumoto, A. Yoshogoe, Y. Terada, K. Kanda, M. Niibe:
“Selective Etching of sp² Carbon in a Diamond-like Carbon Film by Hyperthermal Atomic Oxygen Exposures”
 4th Vac. & Surf. Sci. Conference Asia and Australia, Matsue Japan, October 28-31 (2008).
59. M. Niibe and K. Koida:
“Experiment of Contamination Generation by EUV irradiation with the Use of High-Mass Hydrocarbon Gas”
 Int’l Symp. Extreme Ultraviolet Lithography, Lake Tahoe, USA, September 28-October. 1 (2008).
60. Y. Fukuda, H. Takase, S. Terashima, Y. Watanabe, T. Nakayama, Y. Gomei, T. Aoki, S. Tatsunari. S. Kawata, Y. Kakutani, K. Koida, M. Niibe: **“Contamination Study at EUVA”**
 Int’l Symp. Extreme Ultraviolet Lithography, Lake Tahoe, USA, September 28-October 1 (2008).
61. T. Aoki, Y. Kakutani, S. Matsunari, K. Murakami, S. Kawata, T. Nakayama, S. Terashima, H. Takase, Y. Watanabe, Y. Gomei, Y. Fukuda, M. Niibe:
“Durability of Capped Multilayer Mirrors for Extreme Ultraviolet Lithography Tool”
 Int’l Symp. Extreme Ultraviolet Lithography, Lake Tahoe, USA, September 28-October. 1 (2008).
62. M. Niibe, K. Miyamoto and K. Mochiji,
“Identification of B-K XANES Peaks of BN Thin Film Prepared by Sputtering Deposition”
 5th Int’l Workshop on DV-X α , Himeji, Japan, August 6-8 (2008)
63. M. Niibe, K. Koida and Y. Kakutani:
”Protection and reduction of surface oxidation of Mo/Si multilayers for extreme ultraviolet lithography projection optics by control of hydrocarbon gas atmosphere”
 52nd Int’l Conf. Electron, Ion and Photon Beam Technol. Portland, USA, May-28-30 (2008).
64. Daiji Noda and Tadashi Hattori,
“Development of a New Nano-Micro Solid Processing Technology Based on a LIGA Process and a Next-Generatic Micro Actuator”
 2nd Int’l Symposium on Next-Generation Actuators Leading Breakthroughs, Chiba, Japan, April 17 (2008).
65. Daiji Noda, Yoshifumi Matsumoto, Masaru Setomoto, Daisuke Ochi, and Tadashi Hattori,
“Fabrication of Narrow Pitch and High Aspect Ratio Microcoil for Electromagnetic Microactuators”

- 11th Int'l Conference on New Actuators, Bremen, Germany, June 9-11 (2008).
66. Masaru Setomoto, Yoshifumi Matsumoto, Daiji Noda, and Tadashi Hattori,
“Fabrication of Spiral Micro Coil Lines for Micro Actuators Using X-ray Lithography and Metallization”
 11th Int'l Conference on New Actuators, Bremen, Germany, June 9-11 (2008).
 67. Kyo Tanabiki, Daiji Noda, and Tadashi Hattori,
“Fabrication of the Tapered Structure Using X-ray Diffraction and Applying to LIGA Process”
 Int'l Conference on Electrical Engineering 2008, Okinawa, Japan, June 6-10 (2008).
 68. Hiroshi Tsujii, Daiji Noda, and Tadashi Hattori,
“Fabrication of X-ray Mask with the Silicon Microstructure”
 Int'l Conference on Electrical Engineering 2008, Okinawa, Japan, June 6-10 (2008).
 69. Atsushi Momose, Yoshihiro Takeda, Wataru Yashiro, Daiji Noda, and Tadashi Hattori, **“Sensitivity of X-ray Phase Tomography Based on Talbot and Talbot-Lau Interferometer”** (Invited)
 SPIE Optics + Photonics, San Diego, USA, August 12-14 (2008).
 70. Daiji Noda, Hiroshi Tsujii, Kazuma Shimada, Wataru Yashiro, Atsushi Momose, and Tadashi Hattori,
“Fabrication of High Aspect Ratio X-ray Grating Using X-ray Lithography”
 3rd JSME/ASME Int'l Conference on Material and Processing, Evanston, USA, October 7-10 (2008).
 71. Kazufumi Nishimoto, Naoya Ishizawa, Hiroaki Miyake, Toshiaki Sakai, Satoshi Nishida, Hiroyasu Ueda, Koichi Itoigawa, Daiji Noda, and Tadashi Hattori,
“Processing on Hot Emboss Molding for a Small Capacitive Inclination Sensor”, 3rd JSME/ASME Int'l Conference on Material and Processing, Evanston, USA, October 7-10 (2008).
 72. Yoshitaka Sawa, Kyo Tanabiki, Daiji Noda, and Tadashi Hattori,
“Fabrication of the 3 Dimension Resist Microstructure Using X-ray Diffraction and Applying to LIGA Process”
 3rd JSME/ASME Int'l Conference on Material and Processing, Evanston, USA, October 7-10 (2008).
 73. Daiji Noda, Hiroshi Tsujii, Naoki Takahashi, and Tadashi Hattori,
“Fabrication of X-ray Grating Using X-ray Lithography Technique”
 Pacific RIM Meeting on Electrochemical and Solid-State Science, Honolulu, USA, October 12-17 (2008).
 74. Daiji Noda, Masaru Setomoto, and Tadashi Hattori,
“Fabrication of Microcoil with Narrow and High Aspect Ratio Lines for Electromagnetic Actuators”
 IEEE Int'l Symposium on Micro-Nano Mechatronics and Human Science, Nagoya, Japan, November 6-9 (2008).
 75. Yoshitaka Sawa, Kenji Yamashita, Takeshi Kitadani, Daiji Noda, and Tadashi Hattori, **“Fabrication of High Hardness Micro Mold Using Double Layer Nickel Electroforming”**
 IEEE Int'l Symposium on Micro-Nano Mechatronics and Human Science, Nagoya, Japan, November 6-9 (2008).
 76. Yuta Okayama, Kenji Yamashita, Daiji Noda, and Tadashi Hattori,
“Fabrication of Ultraviolet Range Light Guide Plate”
 IEEE Int'l Symposium on Micro-Nano Mechatronics and Human Science, Nagoya, Japan, November 6-9 (2008).
 77. Naoki Takahashi, Hiroshi Tsujii, Daiji Noda, and Tadashi Hattori,
“Suggestion of New X-ray Mask Using Carbon Substrate”
 IEEE Int'l Symposium on Micro-Nano Mechatronics and Human Science, Nagoya, Japan, November 6-9 (2008).
 78. Daiji Noda, Masaru Setomoto, Yuki Kobayashi, and Tadashi Hattori,
“Fabrication and Estimation of Electromagnetic Type Micro-Actuator with Microcoil”
 SPIE Int'l Symposium on Smart Materials, Nano- and Micro-Smart Systems, Melbourne, Australia, December 9-12 (2008).

(3) Awards

1. T. Watanabe, T. Geun Kim, S. Suzuki, M. Osugi, Y. Fukushima, H. Kinoshita, and T. Mochizuki
“EUV Interference Lithography Employing 11-m Long Undulator as a Light Source”
Best Poster Presentation Award of the International Workshop on EUV Lithography 2008
Int’l. Workshop on EUV Lithography, Maui, Hawaii, USA, Jun. 10-12 (2008).